

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	IS&R	L1	1212	(427/569).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 07:53
2	IS&R	L3	265	(427/573).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 07:55
3	BRS	L4	97795	(chang\$3 or increas\$3 or decreas\$3) same (flow adj3 rate)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 07:57
4	BRS	L5	696	4 same ("SiH.sub.4" or "SiF.sub.4" or "TEOS")	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 07:58
5	BRS	L6	11	5 same (nozzle or nozzles)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 08:46

	Type	L #	Hits	Search Text	DBs	Time Stamp
6	BRS	L7	982	¹⁶ ^{near 8} (first adj (flow adj rate)) same (second ^{1 near} adj (flow adj rate))	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 08:47
7	BRS	L8	8	7 and (breakdown adj3 voltage\$3)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 08:54
8	BRS	L9	982	7 same (second or seconds)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 08:54
9	BRS	L10	28	9 same (nozzle or nozzles)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 09:07
10	IS&R	L12	352	(427/574).CCLS.	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 09:15

L 2 (deposit \$4 or form \$4 or grow \$4) near 2 (layer or film)
 L 1 near 2
 02/06/2003, EAST Version: 1.03.0002

	Type	L #	Hits	Search Text	DBs	Time Stamp
1	BRS	L1	862	(first adj flow adj rate) with (second adj flow adj rate)	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 13:16
2	BRS	L2	52	1 with after	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 13:22
3	BRS	L3	2	2 with plasma	USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B	2003/02/06 13:26

(second! or another or addition of near 2

(nozzle or input or port) near 4

((reactant near 2 gas or reactant) or

(S.H. sub. 7" or "S.F. sub. 4" or

T.L.C.S.K.

US-PAT-NO: 6120606

DOCUMENT-IDENTIFIER: US 6120606 A

TITLE: Gas vent system for a vacuum chamber

----- KWIC -----

a second line connected after said gas regulator, said second line being connected in parallel with said first line, said second line having a second metering valve and an in-line valve in series, after said first line starts to vent said gas into said vacuum chamber, said second line allowing said gas to pass through into said vacuum chamber in a second flow rate higher than said first flow rate for increasing a venting rate of said vacuum chamber by opening said first line and said second line at a same time;

a second line connected after said gas regulator, said second line being connected in parallel with said first line, said second line having a second metering valve and an in-line valve in series, after said first line starts to vent said gas into said vacuum chamber, said second line allowing said gas to pass through into said vacuum chamber in a second flow rate higher than said first flow rate for increasing a venting rate of said vacuum chamber by opening said first line and said second line at a same time;